EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L6	9085	430/5.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 16:58
L7	722	430/4.ccls. not 6	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 16:59
L8	35	(6 or 7) and ((phas$3 or shift$3) near2 (mask or photomask or reticle) or $3PSM) same (substrate or base or surface) same defect$3 same (bump$3 or protru$4 or bulg$3)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 17:00
L9	3	8 and polish$3 same (substrate or base or surface) same (defect$3 or bump$3 or protru$4 or bulg$3)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 17:07
L10	29	8 and etch$3 same (substrate or base or surface) same (defect$3 or bump$3 or protru$4 or bulg$3) not 9	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 17:08
L11	3	8 not 9 not 10	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 17:09
L12	1074	356/489,495,511-514.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 17:16
L13	14	12 and (laser or coherent or coherence) same interference same confocal	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 17:16
L14	2	(laser or coherent or coherence) same interference same confocal same (defect AND (glass or silicon dioxide or silica or SiO".sub.2")) not 9 not 10 not 11 not 13	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 17:24
L15	48	(laser or coherent or coherence) same interference same confocal same (defect OR (glass or silicon dioxide or silica or SiO".sub.2")) not 9 not 10 not 11 not 13 not 14	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 17:31
L16	7	(mask or photomask or reticle) same glass near2 (blank or base or substrate) same (polish$3 or abra$4 or grind$3) same (colloid$2) near2 (silica or silicon dioxide or SiO".sub.2") not 9 not 10 not 11 not 13 not 14 not 15	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 17:32

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L17	15	(mask or photomask or reticle) same glass same (blank or base or substrate) same (polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2") not 9 not 10 not 11 not 13 not 14 not 15 not 16	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 17:36
L18	2960	((mask or photomask or reticle) near3 (phas$3 or shift$3 or reflect$3 or extreme ultraviolet or extreme UV or EUV) or $3PSM) same glass not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 17:42
L19	112	18 and glass same (polish$3 or abra$4 or grind$3) same (silica or silicon dioxide or SiO".sub.2" or SiO$6)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 17:43
L20	185	18 and glass same (polish$3 or abra$4 or grind$3) not 19	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 17:45
L21	646	18 and (6 or 7) and (mask or photomask or reticle or $3PSM) same glass same (blank or base or substrate) not 19 not 20	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 17:58
L22	8	21 and (polish$3 or abra$4 or grind$3) same (silica or silicon dioxide or SiO".sub.2" or silicon oxide or Si oxide)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 17:50
L23	9227	451/36,37,41,42,390.ccls. or 65/60.1,61.ccls. or 427/160,165,290,292.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 17:57
L24	579	23 and (polish$3 or abra$4 or grind$3) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2") not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17 not 19 not 20 not 22	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:02
L25	64	24 and (polish$3 or abra$4 or grind$3) same (pressure or force or load) same glass	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:04
L26	1533	51/308.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:05
L27	5	(24 or 26) and hydroly$4 same (organosilicon or organo silicon or organic silicon or organic Si) same (colloid$2) same (silica or silicon dioxide or SiO".sub.2") not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17 not 19 not 20 not 22 not 25	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:09

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L28	3	(24 or 26) and hydroly$4 same (organosilicon or organo silicon or organic silicon or organic Si) not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17 not 19 not 20 not 22 not 25 not 27	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:14
L29	3	(24 or 26) and hydroly$4 near5 (silica or silicon dioxide or SiO".sub. 2") same (silicon or Si) near5 (organic or polymer) not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17 not 19 not 20 not 22 not 25 not 27 not 28	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:18
L30	20	(24 or 26) and hydroly$4 same (silica or silicon dioxide or SiO".sub. 2") same (silicon or Si) same (organic or polymer) not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17 not 19 not 20 not 22 not 25 not 27 not 28 not 29	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:23
L31	7	(mask or photomask or reticle or $3PSM) same (glass or quartz) same (blank or substrate) same (polish$3 or abra$4 or grind$3 or lap$6) same "pH" not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17 not 19 not 20 not 22 not 25 not 27 not 28 not 29 not 30	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:26
L32	1236071	glass	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:26
L33	265209	polish or polishing or polished	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:26
L34	661235	silica or silicon dioxide or SiO".sub. 2"	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:28
L35	9527	32 and 33 and 34 and "pH"	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:32
L36	2282	33 same "pH" and 32 and 34	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:36
L37	1099	36 and 32 same 34	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:38
L38	310	37 and 33 near10 "pH" and colloidal 34	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:42

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L39	293	(32 and 33 and 34).ti,ab.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:44
L40	9	(38 and 39) not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17 not 19 not 20 not 22 not 25 not 27 not 28 not 29 not 30 not 31	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:51
L41	80	32 same 33 same colloidal 34 same (silicon dioxide or SiO".sub.2") not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17 not 19 not 20 not 22 not 25 not 27 not 28 not 29 not 30 not 31 not 40	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:54
L42	8	41 and 33 same "pH" not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17 not 19 not 20 not 22 not 25 not 27 not 28 not 29 not 30 not 31 not 40	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 18:56
L43	22805	(quartz near3 glass) with (mask or photomask or reticle or substrate or blank or support)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 19:05
L44	7417	(mask or photomask or reticle) with (polish$3 or lap$4)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 19:07
L45	85	43 and 44 and excimer	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 19:07
L46	1277	(mask or photomask or reticle or substrate or blank or support) and ((pressure or weight$3 or load) with ("kg/cm.sup.2" or "g/cm.sup. 2")) same (polish$3 or lap$4)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 19:09
L47	42136	(polish$3 or lap$4) same (quartz or glass)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 19:10
L48	489	46 and 47	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 19:10
L49	52445	colloid$2 near3 34	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 19:14
L50	1666	hydroly$4 with 49	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 19:15
L51	10	48 and 50 not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17 not 19 not 20 not 22 not 25 not 27 not 28 not 29 not 30 not 31 not 40 not 42	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 19:18

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L52	1	45 and 49 not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17 not 19 not 20 not 22 not 25 not 27 not 28 not 29 not 30 not 31 not 40 not 42 not 51	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 19:21
L53	2	45 and 46 not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17 not 19 not 20 not 22 not 25 not 27 not 28 not 29 not 30 not 31 not 40 not 42 not 51 not 52	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 19:29
L54	42	49 and (glass or quartz) same (((pressure or weight$3 or load) with ("kg/cm.sup.2" or "g/cm.sup. 2")) same (polish$3 or lap$4)) not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17 not 19 not 20 not 22 not 25 not 27 not 28 not 29 not 30 not 31 not 40 not 42 not 51 not 52 not 53	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 19:37
L55	25	54 and (surface roughness or root mean square or RMS)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 19:38
L56	139	46 and 47 and 49 not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17 not 19 not 20 not 22 not 25 not 27 not 28 not 29 not 30 not 31 not 40 not 42 not 51 not 52 not 53 not 55	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 19:42
L57	44	56 and (surface roughness or root mean square or RMS)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 19:41
L58	24	57 and "pH"	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 19:41
L59	17	(Koike-Kesahiro or Miyagaki-Junji). in. not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17 not 19 not 20 not 22 not 25 not 27 not 28 not 29 not 30 not 31 not 40 not 42 not 51 not 52 not 53 not 55 not 58	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 19:44
L60	1	(Hoya).as. and (phas$3 or shift$3 or $3PSM) and (defect$3 or protru$4 or bump or bulg$3) and polish$3 and colloid$2 near2 34 and "pH" not 9 not 10 not 11 not 13 not 14 not 15 not 16 not 17 not 19 not 20 not 22 not 25 not 27 not 28 not 29 not 30 not 31 not 40 not 42 not 51 not 52 not 53 not 55 not 58 not 59	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2007/09/18 19:52